

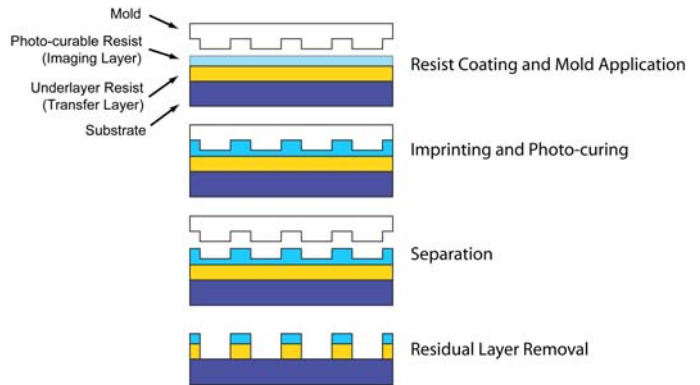
# NXR-3000 Series Underlayer Resists

# Nanoimprint Solutions



Engine for Nanotechnology™

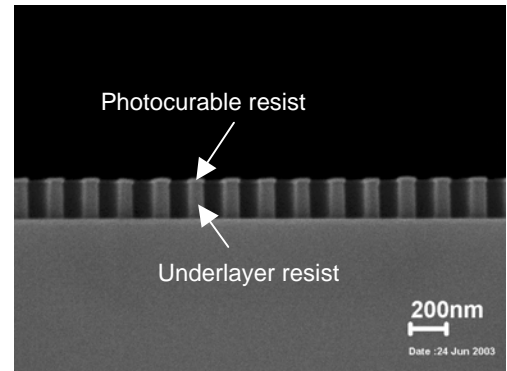
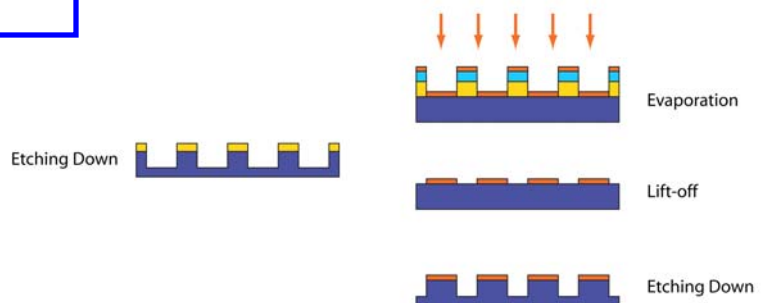
Machines   Masks   Resists   Processes



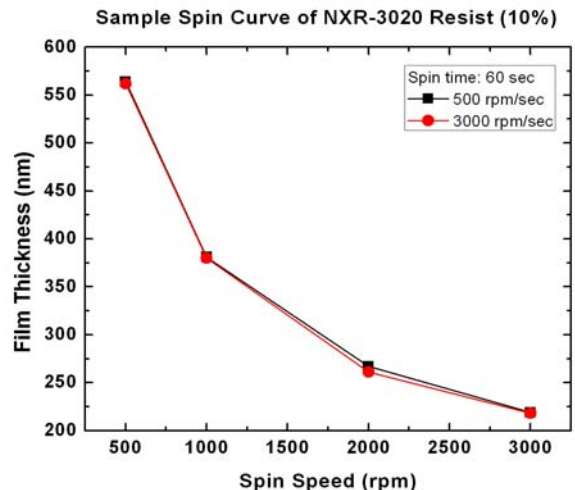
*NXR-3000 series resists are underlayer resists designed to enhance etching resistance and lift-off properties for various nanoimprint applications, and can also be used to planarize the surfaces of substrates. They provide good adhesion to both substrates and NXR-2000 series resists with excellent thermal stability. NXR-3000 series resists significantly enhance the capability of photocurable nanoimprint processes.*

## Key Features

- Excellent thermal stability
- Easy handling and processing
- Planarizing surface
- Strong adhesion to top layer and substrate
- Optimizing direct etch and lift-off processes



NXR-3000 Series	NXR-3010	NXR-3020	NXR-3030
Spin coating	Yes	Yes	Yes
Thickness	100 – 450 nm	80 – 600 nm	150 – 1000 nm
Top layer resist	NXR-2010	NXR-2010	NXR-2030
RIE etch	O <sub>2</sub> RIE	O <sub>2</sub> RIE	O <sub>2</sub> RIE
RIE selectivity to NXR-2000 resist	> 10 : 1	> 10 : 1	> 10 : 1
Planarization	Workable	Workable	Workable
Lift-off Solvent	RCA #1	Methanol or water	Acetone
Resist Removal	RCA #1	Methanol or RCA #1	Acetone or RCA #1



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<http://www.nanonex.com>

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The specifications may be updated without notice.